

L Number	Hits	Search Text	DB	Time stamp
4	1	"6444010"	USPAT	2003/11/28 14:00
5	2	7-193035	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/11/28 14:02
6	17	"193035"	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/11/28 14:02
7	72	silicon adj wafer same ammonia adj gas	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/11/28 14:14
8	78	silicon adj wafer same neutraliz\$4	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/11/28 14:19
9	1958	silicon adj wafer same resistivity	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/11/28 14:22
10	369191	silicon adj wafer same resistivity samd recovery	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/11/28 14:19
11	4	silicon adj wafer same resistivity same recovery	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/11/28 14:20
12	123	silicon adj wafer same resistivity same acid	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/11/28 14:20
13	970	silicon adj wafer same resistivity and impurit\$4	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/11/28 14:22
14	209	silicon adj wafer same resistivity and impurit\$4 and acid and heat	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/11/28 14:22
15	305	silicon adj wafer same resistivity and impurit\$4 and acid and heat\$4	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/11/28 14:22
16	29	silicon adj wafer and resistivity and impurit\$4 and acid and heat\$4 and ammonia adj gas	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/11/28 14:51
18	0	(copper or Cu) same impurit\$4 same silicon adj wafer	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/11/28 14:52
17	98	copper same impurit\$4 same silicon adj wafer	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/11/28 14:53
19	0	copper same impurit\$4 same silicon adj wafer same resitivity	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/11/28 14:53
20	0	impurit\$4 same silicon adj wafer same resitivity	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/11/28 14:54
21	0	impurit\$4 same silicon adj wafer same resitivit\$4	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/11/28 14:54

22	1	silicon adj wafer same resitivit\$4 same (detect\$4 or determin\$4 or analy\$4 or measur\$4 or sense or quantif\$4 or check\$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/11/28 14:55
-	342	silicon adj wafer same sulfuric adj acid	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/11/25 22:36
-	26	(silicon adj wafer same sulfuric adj acid) same between	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/11/25 22:28
-	42	(silicon adj wafer same sulfuric adj acid) same (detect\$4 or determin\$4 or analy\$4 or measur\$4 or sense or quantif\$4 or check\$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/11/25 22:36
-	14	(silicon adj wafer same sulfuric adj acid) same (detect\$4 or determin\$4 or analy\$4 or measur\$4 or sense or quantif\$4 or check\$4) and heat	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/11/25 22:40
-	50	silicon adj wafer same sulfuric adj acid same heat\$4	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/11/25 22:54
-	82	silicon adj wafer same sulfuric adj acid same ammonia	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/11/25 22:56
-	2	silicon adj wafer same sulfuric adj acid same ammonia adj gas	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/11/25 22:57
-	2	silicon adj wafer and sulfuric adj acid same ammonia adj gas	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/11/25 22:58
-	50	sulfuric adj acid same ammonia adj gas same neutral\$6	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/11/25 22:59
-	1	sulfuric adj acid same ammonia adj gas same neutral\$6 and silicon adj wafer	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/11/25 22:59
-	4	sulfuric adj acid same ammonia adj gas same neutral\$6 and silicon	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/11/25 23:23
-	146	silicon adj wafer same impurit\$5 same (Cu or copper)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/11/25 23:24
-	25	silicon adj wafer same impurit\$5 same (Cu or copper) same acid	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/11/25 23:29
-	1	11-321776	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/11/25 23:30
-	12	"321776"	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/11/25 23:30
-	28	"5560857"	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/11/25 23:32
-	4	"5141563"	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/11/25 23:34

-	11	"3761313"	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/11/25 23:34
-	3	6,566,407	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/11/26 16:28